Form Approved REPORT DOCUMENTATION PAGE OMB No. 0704-0188 Public reporting burden for this collection of information is estimated to average 1 hour per response, including the time for reviewing instructions, searching existing data sources, gathering and maintaining the data needed, and completing and reviewing this collection of information. Send comments regarding this burden estimate or any other aspect of this collection of information, including suggestions for reducing this burden to Department of Defense, Washington Headquarters Services, Directorate for Information Operations and Reports (0704-0188), 1215 Jefferson Davis Highway, Suite 1204, Arlington, VA 22202-4302. Respondents should be aware that notwithstanding any other provision of law, no person shall be subject to any penalty for failing to comply with a collection of information if it does not display a currently valid OMB control number. **PLEASE DO NOT RETURN YOUR FORM TO THE ABOVE ADDRESS.** 3. DATES COVERED (From - To) 1. REPORT DATE (DD-MM-YYYY) 2. REPORT TYPE 19-03-2012 **Briefing Charts** 4. TITLE AND SUBTITLE 5a. CONTRACT NUMBER Synthesis and Free Radical Polymerization of Fluorinated Polyhedral Oligomeric Silsesquioxane (F-POSS) Macromers: Precursors for Low Surface Energy Materials **5b. GRANT NUMBER 5c. PROGRAM ELEMENT NUMBER And Devices** 6. AUTHOR(S) **5d. PROJECT NUMBER** Sean M. Ramirez 5f. WORK UNIT NUMBER 23030521 7. PERFORMING ORGANIZATION NAME(S) AND ADDRESS(ES) 8. PERFORMING ORGANIZATION REPORT NUMBER Air Force Research Laboratory (AFMC) AFRL/RZSM 9 Antares Road Edwards AFB CA 93524-7401 9. SPONSORING / MONITORING AGENCY NAME(S) AND ADDRESS(ES) 10. SPONSOR/MONITOR'S ACRONYM(S) Air Force Research Laboratory (AFMC) 11. SPONSOR/MONITOR'S AFRL/RZS NUMBER(S) 5 Pollux Drive Edwards AFB CA 93524-7048 AFRL-RZ-ED-VG-2012-079 12. DISTRIBUTION / AVAILABILITY STATEMENT Distribution A: Approved for public release; distribution unlimited. PA# 12231. 13. SUPPLEMENTARY NOTES For presentation to the Chemistry Department of the Air Force Academy, Colorado Springs, CO, 12 April 2012. 14. ABSTRACT

In this presentation, structures were demonstrated to be reactive towards a variety of dichlorosilanes. Solubility of F-POSS compounds were shown to be influenced by chemical functionality. Functionality was shown to be influential on contact angle measurements. Scientists are currently working on other monomers and polymers for F-POSS. F-POSS compounds have a near limitless potential in producing a variety of new hydrophobic, oleophobic, or omniphobic polymer composites.

15. SUBJECT TERMS

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Synthesis and Free Radical Polymerization of Fluorinated Polyhedral Oligomeric Silsesquioxane (F-POSS) Macromers: Precursors for Low Surface Energy Materials and Devices

Sean M. Ramirez
ERC Inc., Air Force Research Laboratory
Propulsion Directorate
Edwards Air Force Base, CA



AFRL Propulsion Directorate

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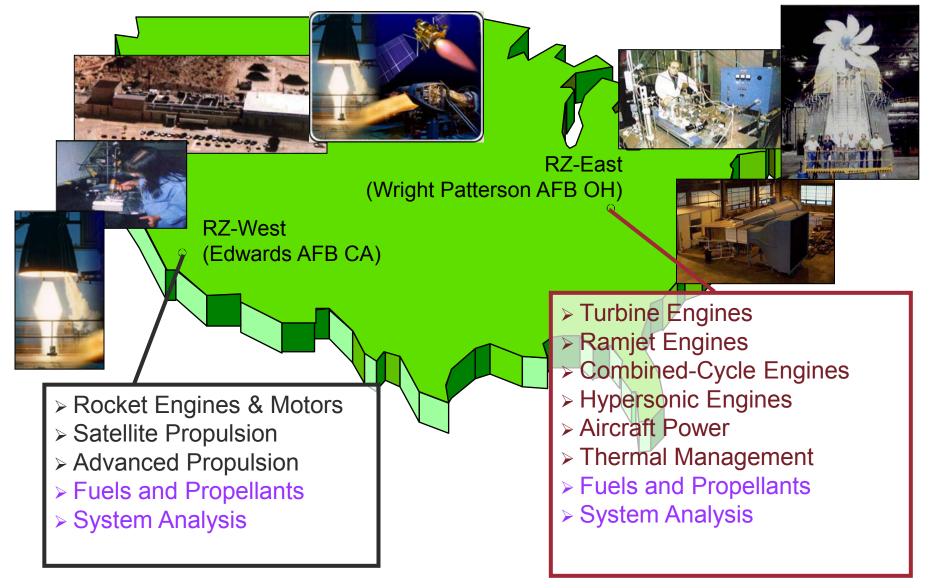
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AFRL Propulsion Directorate

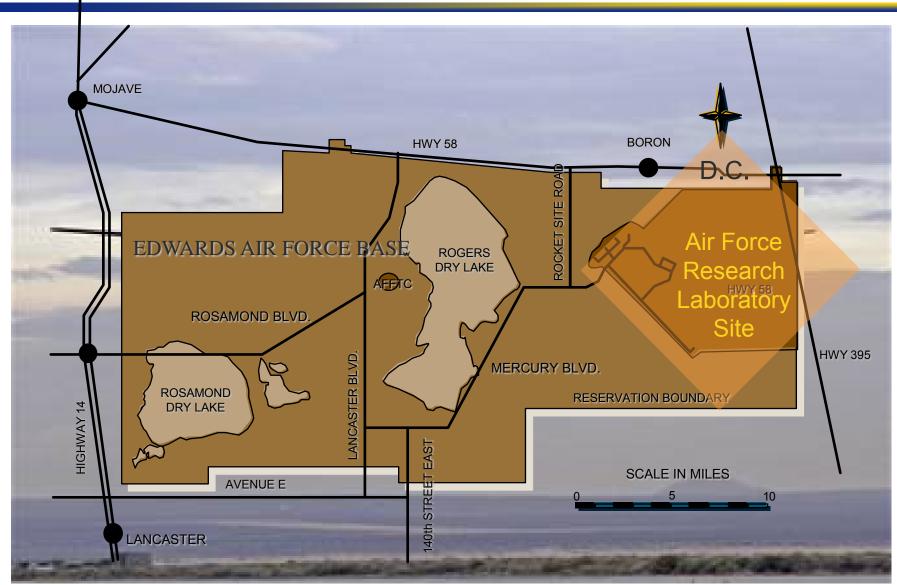






Edwards AFB



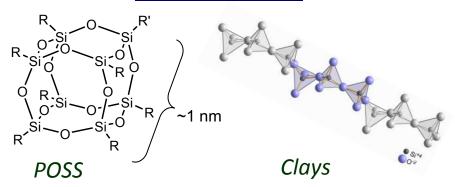




Basic and Applied Research



Basic Research



Basic POSS research funded by AFOSR

Solid Rocket Motors

- Polymers are >50% of inert mass
- Nanocomposites allow significant weight reduction
- Transition target Boost, strategic, & tactical SRMs
- Use possible in other Air Force applications



Atlas V

<u>Liquid Rocket Engines</u>

- Fluorinated polymer nanocomposites
- Reduce cost and improve performance
- Most hydrophobic crystalline solids known
- Superoleophobic surfaces produced
- Fuel separation



Liquid Demo Engine

Polymer Matrix Composites

- Replace metals for mass reduction
- Resistance to oxidation seen in nanocomposite PMCs
- Developing PMC resins for high-temperature applications
- Moisture uptake properties improved with added nanomaterials



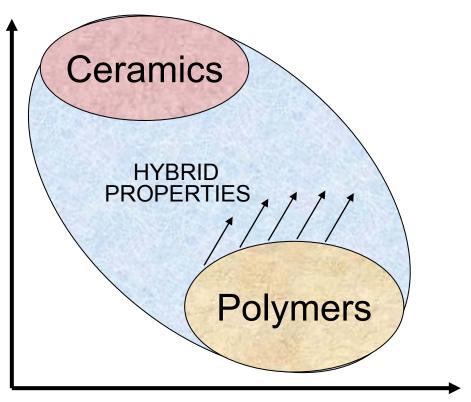
Bushings



Hybrid Inorganic/Organic Polymers



Use Temperature & Oxidation Resistance



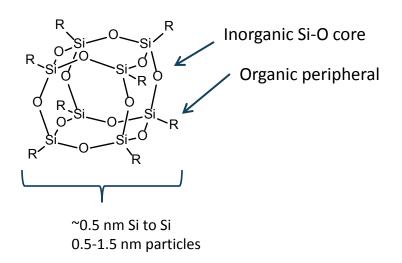
Toughness, Lightweight & Ease of Processing



POSS (RSiO_{1.5})_n



- Organic-inorganic framework
- Well-defined, 3-D nanostructure
- Can carry functional groups
- Thermally and chemically robust
- Used in thermoset and thermoplastic polymers, temperature nanocomposites, coatings, surface modifiers, and many other applications





Introduction to F-POSS



(1,1,2,2-tetrahydroperfluorodecyl)₈Si₈O₁₂ Polyhedral Oligomeric Silsesquioxane (POSS), or fluorodecyl POSS

- hybrid organic-inorganic structure
- well-defined polyhedral architecture
- long-chain fluoroalkyl substituents on periphery of cage

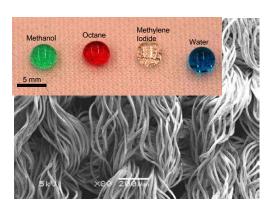
Due to its unique structure, fluorodecyl POSS has one of the lowest surface energies of any crystalline solid currently known

fluorodecyl POSS
 polytetrafluoroethylene
 CF₃ monolayer
 9.3 mN/m
 18-20 mN/m
 6.7 mN/m

Low surface energy and other unique properties of fluorodecyl POSS has enabled the development of various types of tunable non-wetting polymeric surfaces



Superhydrophobic/oleophilic dip-coated fabric Tuteja *et al*, Science, **2007**, 318, 1618



Superamphiphobic dip-coated fabric Choi et al, Adv Mater, **2009**, 21, 2190



Superamphiphobic electrospun surfaces Tuteja *et al*, PNAS, **2008**, 105, 18200



Synthesis of F-POSS



$$R_{f}Si(OEt)_{3} \xrightarrow{EtOH} [R_{f}SiO_{1.5}]_{n}$$

$$R_{f}SiO_{1.5}]_{n}$$

$$R_{f}SiO_{1.5}$$

$$R_{f}SiO_{1.$$



Functional F-POSS (Open-Caged)



- Close-caged structures are accessible and have proven versatile in polymer composites
 - Limitations
 - · Solubility, mechanical robustness (surface abrasion), no sites for functionality
- Open-caged structures would allow for functionalization of F-POSS
 - Open door for use a building block material for low surface energy materials
- Applications
 - Mechanical robust superhydrophobic/oleophobic/omniphobic surfaces
 - Via covalently attached F-POSS to substrate (surface, nanoparticle, polymer matrix)
 - Effects on polymer composite properties
 - Wetting, phase behavior, solubility, etc....

- Open cages lead to functional POSS structures
- Reactions are simple
- High yields typically reported



Methods to Produce Incompletely Condensed Silsesquioxanes



- Bottom-up approach
 - Acid or base mediated from RSiCl₃ or RSi(OR)₃
 - Condensation reaction
 - Balance of stoichiometry, temperature, reaction time, patience, and luck
 - Stopping POSS synthesis early, before cages closes
 - More common approach

- Top-down Approach
 - Strong acid or base mediated
 - Starting from a POSS cage
 - Conversion of Si-O-Si bonds
 to Si-O (-) C(+) or Si-OH bonds
 - Opening up POSS cage

Which method can be applied to F-POSS?



Synthesis of F-POSS-(OH)₃



7 RSi<sub>(OCH₂CH₃₎₃ + 3 BASE + 12 H₂O
$$\frac{R = CH_2CH_2(CF_2)_7CF_3}{\text{solvent, temp.}}$$</sub>

$$R = CH_{2}CH_{2}(CF_{2})_{n}CF_{3}$$

$$R = CH_{2}CH_{2}(CF_{2})_{n}CF_{3}$$

$$R = CH_{2}CH_{2}(CF_{2})_{n}CF_{3}$$

- Synthesis discussed in patents*
- Works for trifluoropropyl groups
- Solubility is critical in this reaction
- Fluorinated compounds not miscible in most organics once condensation begins to occur
- Does not work for long-chain F-POSS
- Tried under various conditions
 - Solvent, temperature, reaction time, base

- Open cages lead to functional POSS structures
- Reactions are simple
- High yields typically reported

*Yamashita, Y.; Hayashi, K.; Ishihara, M.; (Mitsubishi Materials Corp., Japan; Dai Nippon Toryo Co., Ltd.). Application: JP, 2000; pp 12 pp. Yamashita, Y.; Hayashi, K.; Ishihara, M.; (Mitsubishi Materials Corp., Japan; Dai Nippon Toryo Co., Ltd.). Application: JPJP, 2000; pp 9 pp.



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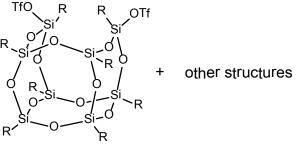
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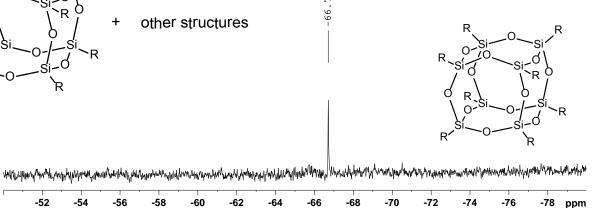
Which method can be applied to F-POSS?



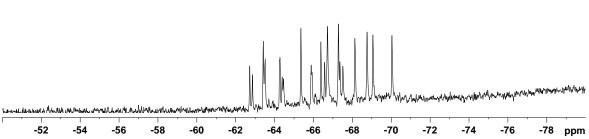
Initial Reactions with Triflic Acid







- Fluorodecyl T₈
- Reacted with triflic acid to open cage structure
- Structures analyzed with ²⁹Si NMR
- Equivalents of triflic acid to POSS cage is important to success of reaction
- Disappointing results



²⁹Si NMR taken in fluorinated solvent

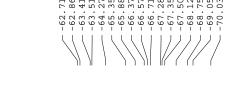


Synthesis of F-POSS-(OTf)₂

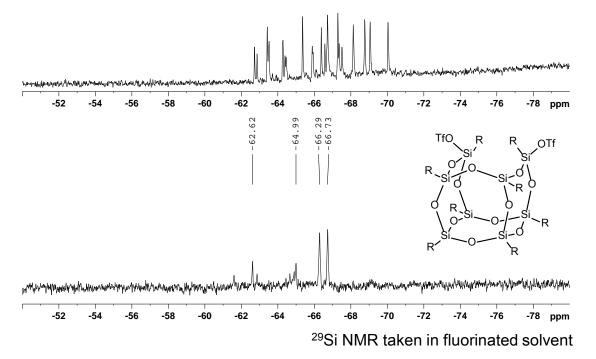


$$\mathsf{R} = \mathsf{CH}_2 \mathsf{CH}_2 (\mathsf{CF}_2)_7 \mathsf{CF}_3$$

- After a little bit of refining
- An open cage structure is partially visible
- Starting material is still present
- Reaction not very clean
- Si ratio (1:1:2)



Mixture of unknown incompletely caged silsesquioxanes and resin



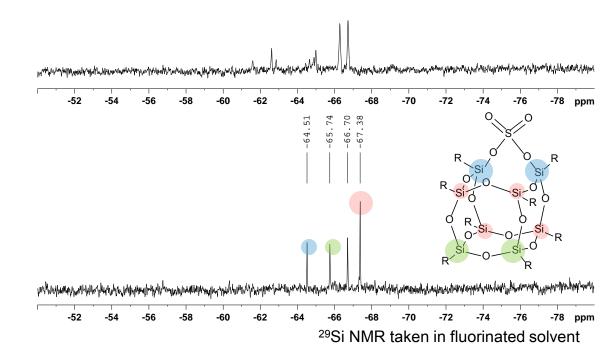


Synthesis of F-POSS-SO₂



$$R = CH_2CH_2(CF_2)_7CF_3$$

- Bridge sulfate cleans up reaction
- Structure significantly more stable than then F-POSS-(OTf)₂, however still difficult to isolate
- Removal of starting material extremely difficult
- Si ratio (1:1:2)





Synthesis of F-POSS-(OH)₂



R OH HO R

Si O Si O Si R

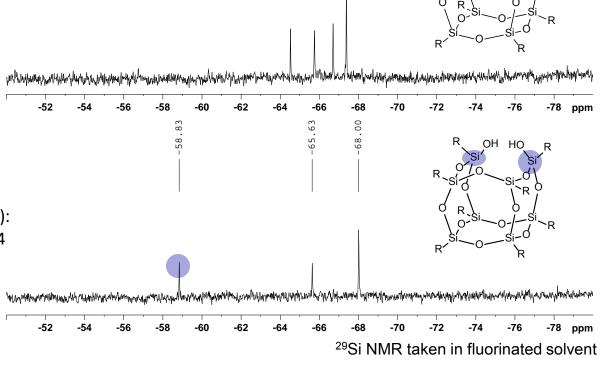
O Si O Si R

R Si O Si O R

R Si O R

 $R = CH_2CH_2(CF_2)_7CF_3$

- Acidic conditions are used to remove the bridge sulfate complex
- Silanol peak at -58.8 ppm
- F-POSS-(OH)₂ is more stable than both
 F-POSS-(OTf)₂ and F-POSS-SO₂
- Anal. Calcd. for C₈₀H₃₄F₁₃₆O₁₃Si₈ (found):
 C, 23.94 (23.99), H, 0.85 (0.75), F, 64.44 (64.72)
- Dehydration of disilanol leads to T₈ formation
- Si ratio (1:1:2)





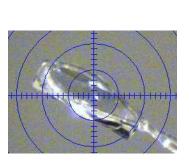
Incompletely Condensed Silsesquioxane

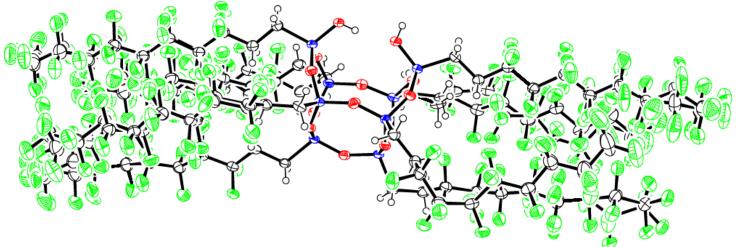




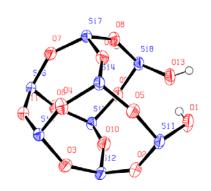
X-Ray Crystal Structure of Disilanol

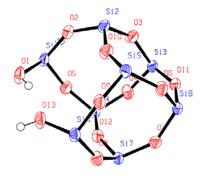






- Crystal structure is dimeric via intra- and intermolecular hydrogen bonding between silanols.
- M_r =,monoclinic, space group P2(1)/c , a=11.84(10) Å, b=57.11(6) Å, c=19.06(2) Å, α = 90.00°, β =92.21(10)°, γ =90.00°, V= 12878(2) Å³







Edge Capping Reactions



$$\begin{array}{c} R & OH & HO & R \\ R & Si & O & Si & Si \\ R & Si & O & Si & R \\ \hline \\ R & Si & O & Si & R \\$$

 $R = CH_2CH_2(CF_2)_7CF_3$

 $R_1 = CH_3$

 $R_2 = CH_2CH_2CH_2OC(O)CHCH_2$

- Edge capping reactions typically have 40-70% yield
- Main side product is starting material (recycled)
- Disilanol can revert back to closed cage during reaction
- Reactions take 5-10 minutes



Edge Capping Reactions

 R_2



ОН НО

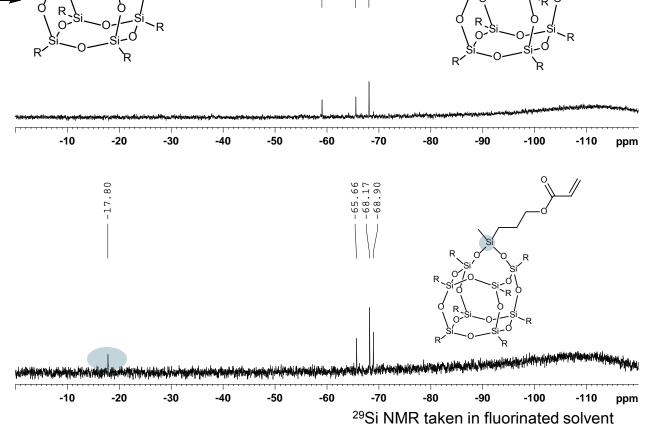
$$\begin{array}{c} R & OH & HO & R \\ Si & O & Si & O \\ R & Si & O & Si & R \\ \hline \\ R & Si & O & Si & R \\ \hline \\ R & Si & O & Si & R \\ \hline \\ R & R & R & R \\ \end{array}$$

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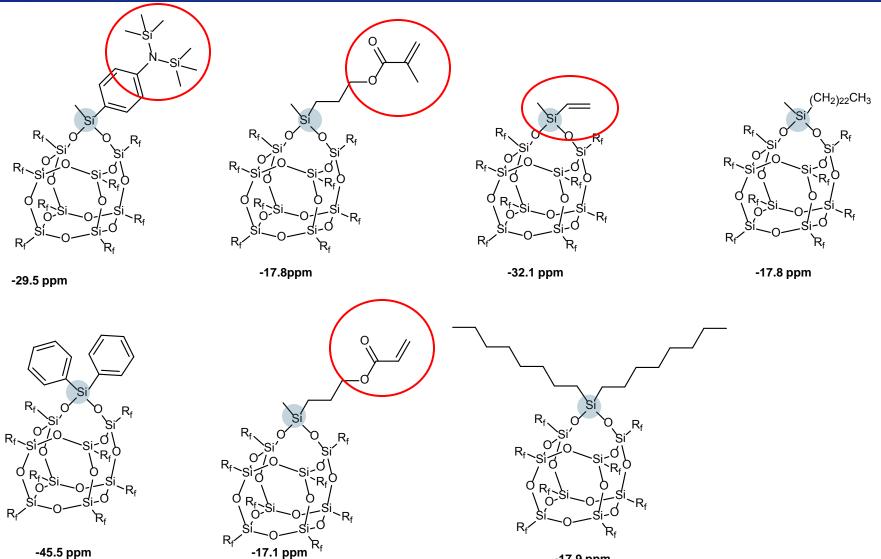
- Typically 40-70% yield
- Main side product is starting material (recycled), formed during base addition
- Disilanol can revert back to closed cage during reaction
- Reactions take 5-10 minutes
- Si ratio (1:2:2:4)
- New Si peak!





F-POSS Structures Synthesized





-17.9 ppm



F-POSS Silane Coupling Reaction



- Chlorosilyl-functional fluoroPOSS compound synthesized from the Pt(II) catalyzed hydrosilyation of vinyl-functional fluoroPOSS and dimethylchlorosilane
- Desired compound successfully synthesized in high yield
- •Characterized by ¹H, ¹³C, ¹⁹F, and ²⁹Si NMR



Introduction to F-POSS



(1,1,2,2-tetrahydroperfluorodecyl)₈Si₈O₁₂ Polyhedral Oligomeric Silsesquioxane (POSS), or fluorodecyl POSS

- hybrid organic-inorganic structure
- well-defined polyhedral architecture
- long-chain fluoroalkyl substituents on periphery of cage

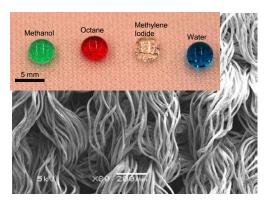
Due to its unique structure, fluorodecyl POSS has one of the lowest surface energies of any crystalline solid currently known

fluorodecyl POSS
 polytetrafluoroethylene
 CF₃ monolayer
 9.3 mN/m
 18-20 mN/m
 6.7 mN/m

Low surface energy and other unique properties of fluorodecyl POSS has enabled the development of various types of tunable non-wetting polymeric surfaces



Superhydrophobic/oleophilic dip-coated fabric Tuteja *et al*, Science, **2007**, 318, 1618



Superamphiphobic dip-coated fabric Choi et al, Adv Mater, **2009**, 21, 2190



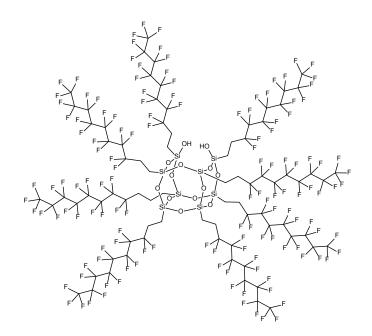
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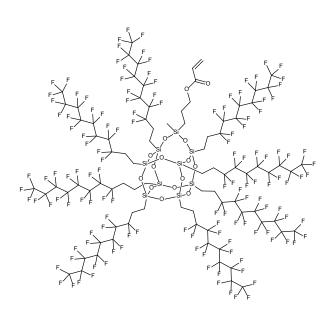


Contact Angle Measurements



- Non-wetting surfaces can be developed by a combination of three parameters
 - Chemical functionality (high fluorine content)
 - Roughness (micro- and nanoscale)
 - Surface Geometry (re-entrant curvature)
- What type of influence will functional groups have on F-POSS surface properties?
- Solvent impact?





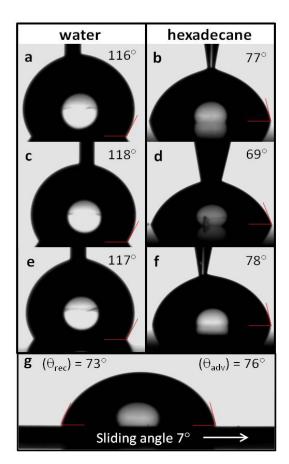


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- What type of influence will functional groups have on F-POSS surface properties?
- Solvent impact?

$$H_3C(CH_2)_7$$
 Si $(CH_2)_7CH$ R_f Si Si Si Si R_f Si Si Si R_f Si Si R_f Si Si R_f Si Si Si R_f Si Si Si R_f Si Si Si Si Si R_f

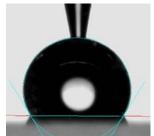


Static contact angles of Si wafer surfaces coated with compounds **disilanol** (a) and (b), **dioctyl** (c) and (d), and **diphenyl** (e) and (f). Image of hexadecane droplet $(10\mu L)$ rolling off surface coated with compound **diphenyl** (g).



Dynamic Contact Angle Measurements





Functional Group on F-POSS	water		hexadecane	
	(θ_{adv})	$(\theta_{\rm rec})$	(θ_{adv})	$(\theta_{\rm rec})$
F-POSS*	$124 \pm 0.5^{\circ}$	$109.6 \pm 0.7^{\circ}$	$79.1 \pm 0.4^{\circ}$	$65.1 \pm 0.5^{\circ}$
Si-(OH) ₂	$116.8 \pm 0.4^{\circ}$	$111 \pm 0.6^{\circ}$	$77.4 \pm 0.4^{\circ}$	$74.4 \pm 0.8^{\circ}$
Si-(CH ₃)(CH=CH ₂)	$116.2 \pm 0.4^{\circ}$	$100.6 \pm 0.8^{\circ}$	$78.4 \pm 0.3^{\circ}$	$70.6 \pm 2.3^{\circ}$
Si((CH ₃)((CH ₂) ₃ OC(O)CCH=CH ₂)	118.2 ± 1.0°	$90.6 \pm 1.0^{\circ}$	$76.8 \pm 0.3^{\circ}$	64.8 ± 1.0°
Si-(CH ₃)((CH ₂) ₃ OC(O)C(CH ₃)=CH ₂)	$117.1 \pm 0.6^{\circ}$	93.8 ± 1.5°	$78.1 \pm 0.4^{\circ}$	63.0 ± 1.2°
Si-(CH ₃)((CH ₂) ₂₂ CH ₃)	$117.9 \pm 0.4^{\circ}$	96.9 ± 1.9°	$78.0 \pm 0.4^{\circ}$	$16.2 \pm 5.5^{\circ}$
$Si-(C_6H_5)_2$	$116.2 \pm 0.4^{\circ}$	$110.5 \pm 0.5^{\circ}$	$76.0 \pm 0.8^{\circ}$	$73.2 \pm 0.4^{\circ}$
Si-((CH ₂) ₇ CH ₃) ₂	117.9 ± 0.5°	$95.5 \pm 0.4^{\circ}$	69.1 ± 1.2°	23.1 ± 1.2°

Samples (10 mg/mL) were spin casted on oxygen-plasma cleaned Si wafers at 900 rpm for 30 seconds. Contact angle measurements were run in triplicate. Surface roughness < 5nm (AFM and Optical Profilometry).



Free Radical Polymerization



A (Monomer)		k.		
AAAAAAAAAA		Initiator — K _d → 2 I•		
-(-A-) n	Initiation	1. + Monomer $\frac{k_i}{}$ \rightarrow P_{n^*}		
A ⁺ B ₍ Monomers ₎ ABAABABAB	Propogation	$P_{n^{\bullet}}$ + Monomer $\xrightarrow{k_p}$ $P_{n^{\bullet}}$		
	Termination	2 Radicals — k _t → Polymer		
	AAAAAAAAAAAAAAAAAAAAAAAAAAAAAAAAAAAAAA	AAAAAAAAAAAAAAAAAAAAAAAAAAAAAAAAAAAAAA		

-Monomers make polymers

AAAAAABBBBBBBB

- -Multiple different types of monomers in a polymer make copolymers
- -Choosing a type of monomer will decide what type of polymer you have -trash bags, cotton, paint, DNA, protein, plastic bottles, etc.....most things you use in your life



Free Radical Polymerization



Initiation
$$k_d \rightarrow 21$$
.

Initiation $l_i + Monomer k_i \rightarrow P_{n^*}$

Propogation $l_i + Monomer k_p \rightarrow P_{n^*}$

Termination $l_i + Monomer k_p \rightarrow P_{n^*}$

Polymer

Example: Polystyrene

$$N=N$$
 heat $2 \cdot$ $+ N_2$ $+ N_2$

Ethylene glycol (monomer) (antifreeze)

Polyethylene glycol

Now MW (laxatives, Jubricants, toothpaste binder)

Higher MW (medical uses, paintballs, etc.)

- Standard polymerization method
- Simple, cheap, easy
- Does not allow for much control
- No block copolymers
- molecular weight difficult to control

Two most important factors for polymers:

- 1) Structure
- 2) Molecular Weight



Reversible Addition-Fragmentation chain Transfer (RAFT) polymerization



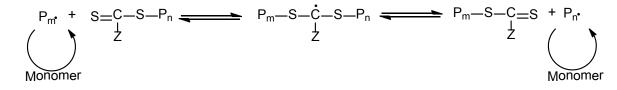
Initiation

Propogation

Termination

$$P_n$$
 + $S=C-S-R$ \longrightarrow $P_n-S-\dot{C}-S-R$ \longrightarrow $P_n-S-C=S+R$.

$$P_{n^{\bullet}}$$
 + Monomer \longrightarrow $P_{n^{\bullet}}$



2 Radicals _____ Dead polymer

Chain Transfer Agent

RAFT Polymerization

- Controlled polymerization
- Allows for block copolymers
- •Tune molecular weight

Chiefari, J.; Chong, Y. K.; Ercole, F.; Krstina, J.; Jeffery, J.; Le, T. P. T.; Mayadunne, R. T. A.; Meijs, G. F.; Moad, C. L.; Moad, G.; Rizzardo, E.; Thang, S. H. Living Free Radical Polymerization by Reversible Addition-Fragmentation Chain Transfer: The RAFT Process. *Macromolecules* 1998, *31*, 5559–5562



Free Radical Copolymerizations



- Standard free radical polymerization of methyl methacrylate and MMA-F-POSS monomers:
 - F-POSS monomer is active towards polymerization
 - F-POSS incorporation (1-20% by weight)
 - Molecular weights range from 10-50,000 g/mol
 - Higher F-POSS and polymerization causes problems



RAFT Copolymerizations



- Controlled/"living" free radical polymerization of methyl methacrylate, CPD, and MMA-F-POSS monomers:
 - Promising results with molecular weights ranging from 20-40,000 gm/mol
 - Narrow polydispersity indices (1.04-1.1)



Summary



- Structures were demonstrated to be reactive towards a variety of dichlorosilanes
- Solubility of F-POSS compounds were shown to be influenced by chemical functionality
- Functionality was shown to be influential on contact angle measurements
- Currently working on other monomers and polymers for F-POSS
- F-POSS compounds have a near limitless potential in producing a variety of new hydrophobic, oleophobic, or ominiphobic polymer composites.
 - Reaction mechanisms, polymer composites, block copolymers, etc....



Acknowlegdements



The Polymer Working Group at Edwards Air Force Base:

Dr. Joseph Mabry

Mr. Pat Ruth

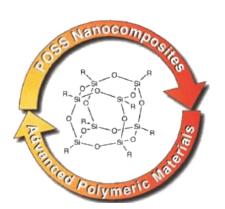
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Mr. Raymond Compos



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Mr. Kevin Lamison

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Ms. Dana Pinson

Capt. Rebecca Stone

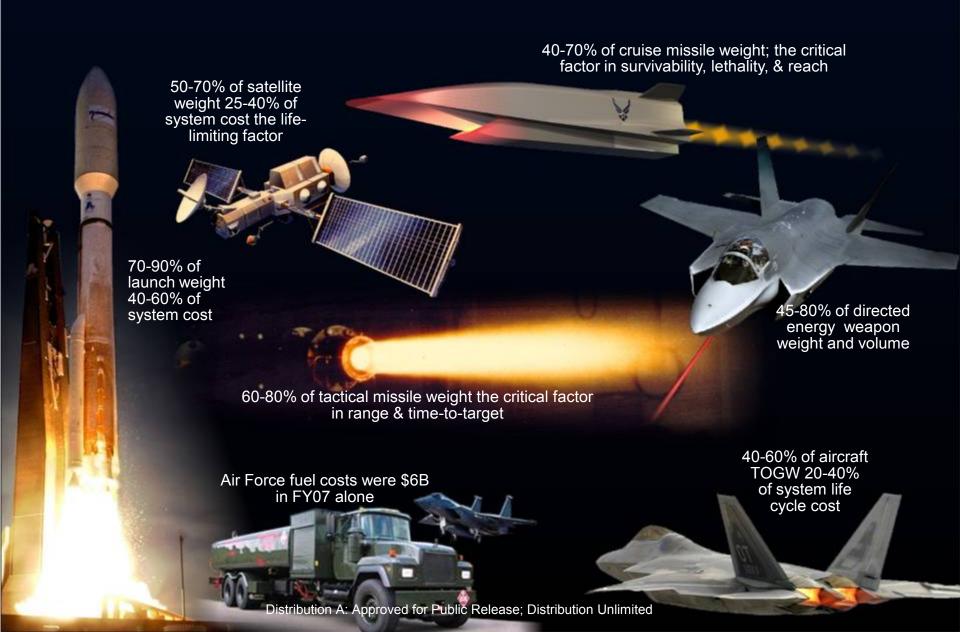
We thank Peter Müller at the Massachusetts Institute of Technology (MIT) and the American Crystallography Association (ACA) summer course for their assistance with small molecule X-ray crystal structure determination and refinement.

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Air Force Research Laboratory, Propulsion Directorate



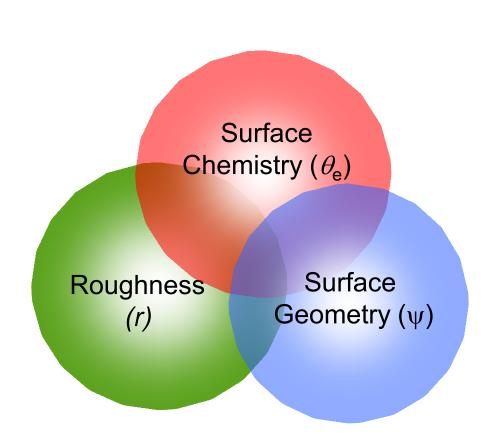
Propulsion & Power are Important!

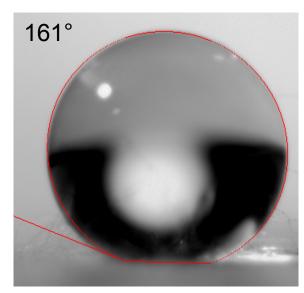




Designing Superoleophobic Surfaces

- Goal: a design framework for constructing super-repellent surfaces
- Demonstrated electrospun mats (single step process)
- Three key ingredients





Superhydrophobic $\theta > 150^{\circ}$

PMMA + 44 wt% POSS electrospun coating (beads on a string) morphology